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## THE UNITED STATES PATENT AND TRADEMARK OFFICE

## In re Applicant:

Justin K. Brask et al.

§ Art Unit: 2811

Serial No.: 10/622,955

§ Examiner: Sara W. Crane

Filed: July 18, 2003

§ Atty Docket: ITL.1021US  
P16708For: Etching Metal Silicides  
and Germanides

§ Assignee: Intel Corporation

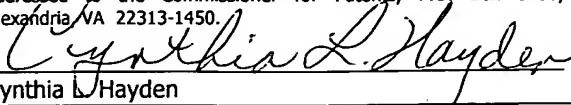
§

**Mail Stop Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY TO PAPER NO. 01102005**

Sir:

In response to the office action mailed January 14, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: <u>March 15, 2005</u>
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as <b>first class mail</b> with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden